Correction: Atomic layer deposition of a MoS₂ film

Cite this: *Nanoscale*, 2014, **6**, 14002

Lee Kheng Tan,^{a,b} Bo Liu,^c Jing Hua Teng,^b Shifeng Guo,^b Hong Yee Low^d and Kian Ping Loh^{*a}

DOI: 10.1039/c4nr90076f

www.rsc.org/nanoscale

Correction for 'Atomic layer deposition of a MoS₂ film' by Lee Kheng Tan *et al.*, *Nanoscale*, 2014, **6**, 10584–10588.

(1) There is an error to the existing author list. The correct list should be:

Lee Kheng Tan,^{‡ab} Bo Liu,^{‡c} Jing Hua Teng,^b Shifeng Guo,^b Hong Yee Low,^d Hui Ru Tan,^b Christy Yuen Tung Chong,^b Ren Bin Yang,^b and Kian Ping Loh^{*a}

(2) There is an error in the Acknowledgements. It should read:

We thank the Institute of Materials Research and Engineering under the Agency for Science, Technology and Research (A*STAR) Singapore as well as the Singapore-Berkeley Research Initiative for Sustainable Energy (SinBeRISE) CREATE Program for the financial support. We are grateful to Mr Lim Poh Chong for his assistance in XRD, Ms June Ong for her assistance in XPS and Dr Liu Hong Fei and Dr Jia Min Chin for their advice.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

^aDepartment of Chemistry and Graphene Research Centre, National University of Singapore, 3 Science Drive 3, Singapore 117543. E-mail: chmlohp@nus.edu.sg

^bA*STAR Institute of Materials Research and Engineering, 3 Research Link, Singapore 117602

^cDepartment of Physics and Graphene Research Centre, National University of Singapore, 2 Science Drive 3, Singapore 117551

^dSingapore University of Technology and Design, 20 Dover Dr, Singapore 138682